10/009,884

	10/009,8			/
L Number	Hits		DB	Time stamp
1	45	(' mears (coacys varings))	USPAT	2004/09/03 11:06
i		and ((thiocyanic adj acid) (thiosulfuric		
		adj acid) thiourea thio\$1ehter thiol		
		(sulfur near3 halide) (sulfur near3		
2	1685	oxyhalide) (halogenosulfonic))		
-	1003	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:41
		surface adj treatment) and ((thiocyanic		
	1	adj acid) (thiosulfuric adj acid) thiourea thio\$lehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
	ŀ	(halogenosulfonic))		
3	2676		USPAT;	2004/00/02 10 41
		surface adj treatment) and ((thiocyanic	US-PGPUB:	2004/09/03 10:41
		adj acid) (thiosulfuric adj acid) thiourea	EPO; JPO;	
		thio\$1ehter thiol (sulfur near3 halide)	DERWENT;	
		(sulfur near3 oxyhalide)	IBM TDB	
	İ	(halogenosulfonic))		
4	96	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:41
		surface adj treatment) and ((thiocyanic		1 2001, 03, 03 10.41
		adj acid) (thiosulfuric adj acid) thiourea		
		thio\$1ehter thiol (sulfur near3 halide)		
	·	(sulfur near3 oxyhalide)		
_		(halogenosulfonic)) and ink\$1jet		
5	928	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:55
		surface adj treatment) and ((thiocyanic		
		adj acid) (thiosulfuric adj acid) thiourea		
		thio\$1ehter (sulfur near3 halide) (sulfur		
6	96	near3 oxyhalide) (halogenosulfonic))		
	, ,	<pre>(((over\$1print\$3 near3 (coat\$3 varnish\$3)) surface adj treatment) and ((thiocyanic</pre>	USPAT	2004/09/03 10:51
		adj acid) (thiosulfuric adj acid) thiourea		
		thio\$lehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
		(halogenosulfonic)) and ink\$1jet) not		
		((over\$1print\$3 near3 (coat\$3 varnish\$3))		
		and ((thiocyanic adj acid) (thiosulfuric		
	Ì	adj acid) thiourea thio\$1ehter thiol		
	1	(sulfur near3 halide) (sulfur near3		1
-	_	<pre>oxyhalide) (halogenosulfonic)))</pre>		
7	5	(("3147301") or ("3033833") or ("2914499")	USPAT	2004/09/03 10:52
8	7	or ("2923734") or ("3024221")).PN.		
°	′	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT	2004/09/03 10:56
		and ((thiocyanic adj acid) (thiosulfuric adj acid) thiourea thio\$1ehter (sulfur		
		near3 halide) (sulfur near3 oxyhalide)		
		(halogenosulfonic))		
9	7	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/03 10:56
		and ((thiocyanic adj acid) (thiosulfuric	US-PGPUB;	2004/03/03 10:36
		adj acid) thiourea thio\$1ehter (sulfur	EPO; JPO;	
		near3 halide) (sulfur near3 oxyhalide)	DERWENT;	
10	1	(halogenosulfonic))	IBM TDB	
10	7	<pre>(over\$1print\$3 near3 (coat\$3 varnish\$3))</pre>	USPAT;	2004/09/03 11:06
		and thiourea	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
_	1 4	/ / U.C. 6.7.7.0.0.C.U.)	IBM_TDB	
	14	(("6677006") or ("6596378") or ("6589635")	USPAT	2004/09/02 17:01
	ļ	or ("6698875") or ("6555207") or ("6517929") or ("6565952") or ("6652171")		
	1	or ("6548150") or ("6173646") or		
1	1	("6245422") or ("6174611") or ("5662997")		
		or ("5560771") or ("5421871")).PN.		
- !	5497	((427/258) or (427/261) or (427/265) or	USPAT;	2004/09/02 17:07
1	i	(427/288) or (427/407.1) or	US-PGPUB;	2004/03/02 17:07
		(427/411)).CCLS.	EPO; JPO;	
			DERWENT;	
1				

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_	0	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/02 17:09
		same (sulfur thiocyanic thiosulfuric	US-PGPUB;	
		thiourea thio\$1ehter thio1)	EPO; JPO;	
	1		DERWENT;	
			IBM_TDB	
-	1041	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/02 17:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
_	119	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/02 17:11
ļ		and (sulfur thiocyanic thiosulfuric	US-PGPUB;	
		thiourea thio\$1ehter thio1)	EPO; JPO;	
		,,	DERWENT;	
			IBM TDB	
_	5	((over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/02 17:12
		and (sulfur thiocyanic thiosulfuric	EPO; JPO;	2001,03,02 11.12
		thiourea thio\$lehter thiol)) and ink\$ljet	DERWENT	
_	119	(over\$1print\$3 near3 (coat\$3 varnish\$3))	USPAT;	2004/09/02 17:31
	119	and (sulfur (thiocyanic adj acid)	US-PGPUB;	2004/05/02 17.51
		(thiosulfuric adj acid) thiourea	EPO; JPO;	
		thio\$lehter thiol (sulfur near3 halide)	DERWENT;	
		(sulfur near3 oxyhalide)	1	
		(halogenosulfonic))	IBM_TDB	
	5	((over\$1print\$3 near3 (coat\$3 varnish\$3))	HCDAM.	2004/09/02 17:12
-	,		USPAT;	2004/09/02 17:12
		and (sulfur (thiocyanic adj acid)	EPO; JPO;	
		(thiosulfuric adj acid) thiourea	DERWENT	
		thio\$1ehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
		(halogenosulfonic))) and ink\$1jet		0004/00/00 45 45
-	91	1 ,	USPAT	2004/09/02 17:45
		and (sulfur (thiocyanic adj acid)		
1		(thiosulfuric adj acid) thiourea		
		thio\$1ehter thiol (sulfur near3 halide)		
		(sulfur near3 oxyhalide)		
		(halogenosulfonic))		
_	143	(over\$1print\$3 near3 (coat\$3	USPAT;	2004/09/02 17:32
		varnish\$3))[ti]	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	0	((over\$1print\$3 near3 (coat\$3	USPAT;	2004/09/02 17:32
		varnish\$3))[ti]) and (sulfur (thiocyanic	US-PGPUB;	
		adj acid) (thiosulfuric adj acid) thiourea	EPO; JPO;	
		thio\$1ehter thiol (sulfur near3 halide)	DERWENT;	
		(sulfur near3 oxyhalide)	IBM TDB	
		(halogenosulfonic))		
-	0	(over\$1print\$3 near3 (coat\$3	USPAT;	2004/09/02 17:32
		varnish\$3))[ti] and (sulfur (thiocyanic	US-PGPUB;	
1		adj acid) (thiosulfuric adj acid) thiourea	EPO; JPO;	
1		thio\$1ehter thiol (sulfur near3 halide)	DERWENT;	
		(sulfur near3 oxyhalide)	IBM TDB	
		(halogenosulfonic))		
L		(managamobalitation)	I	1